



PATENT
Atty. Docket No.: AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

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JPW

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
BEFORE THE BOARD OF PATENT APPEALS AND INTERFERENCES**

In re Application of: Buie et al.

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Serial No.: 10/024,958

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Confirmation No.: 3439

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Filed: December 18, 2001

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For: Etch Process for Photolithographic Reticle Manufacturing with Improved Etch Bias

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MAIL STOP APPEAL BRIEF-PATENTS
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING 37 CFR 1.8	
<p>I hereby certify that this correspondence is being deposited on June 2, 2005, with the United States Postal Service as First Class Mail in an envelope addressed to: Mail Stop Appeals Brief-Patents, Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.</p>	
<u>6/2/05</u> Date	<u>Kirin L. Zabel</u> Signature

Dear Sir or Madam:

REPLY BRIEF

Applicants submit this Reply Brief to the Board of Patent Appeals and Interferences in response to the Examiner's Answer dated April 7, 2005, which Examiner's Answer vacates Examiner's Answer dated December 2, 2004. Please charge any fees that may be required to make this Reply Brief timely and acceptable to the Patent Office, to Deposit Account No. 20-0782/4213P1/KMT.

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